



PHOTOGILE® POU PHOTOCHEMICAL DISPENSE SYSTEM FILTERS

UPE, Nylon, or Multi-Membrane filters for use in photolithography dispense systems and independent manifolds

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POINT-OF-USE FILTERS FOR USE IN PHOTORESIST DISPENSE PUMPS AND SYSTEMS

Photogile® Point-of-Use Filters are ideal for use in lithography photoresist dispense pumps and systems.

The filters are available with UPE (Ultra-High Molecular Weight Polyethylene), Nylon 6,6, or Multi purification membranes to ensure rapid startup for selected photoresists, coatings, and solvents, including ArF, BARC, KrF, top coat, and pre-thinners.

Photogile POU filters ensure excellent retention, cleanliness and high chemical compatibility to meet the critical demands in semiconductor processes. These low hold-up volume filters minimize chemical waste.

Cobetter's superior cleaning of the high purity HDPE (high-density polyethylene) support/core/gage/endcaps/shell ensures high cleanliness.

Cobetter Photogile filters are available in a wide variety of retention ratings to meet your process requirements.

FEATURE	BENEFIT
Available in UPE, Nylon, and Multi-Membrane Configurations	UPE and nylon wets out easily with most solvents and resists.
	UPE highly efficient removal of hard and soft particles
Low hold-up volume	Reduces expensive photochemical waste
Industry Standard Size/Fitting Connections	Ideal for use in a variety of photodispense systems and independent manifolds.
Available with or without o-ring	Provides installation flexibility to compatible dispense systems and manifolds
HDPE supports and structure	High chemical compatibility
	High cleanliness, including low metal extractables
Prewet option	Reduces pre-operation time
	Easy start up with aqueous-based solutions
SPECIFICATIONS	
Filter media	UPE, Nylon 6,6, or Multi (dual layer nylon + UPE)
Supports/core/cage/end caps/ Shell	HDPE
O-rings (cartridge only)	Kalrez® or FFKM
Max. operating temperature	40°C
Max. operating pressure	0.34 MPa (3.4 bar, 49 psi) at 25°C

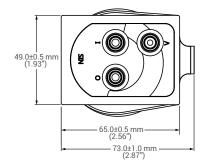


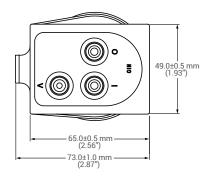


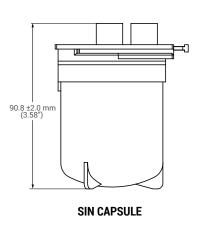
Typical Applications

- · Photoresist Filtration
- Solvent Filtration -ArC,F, KrF, BARC, pre-thinners
- Top Coats

PHOTOGILE POU DIMENSIONS

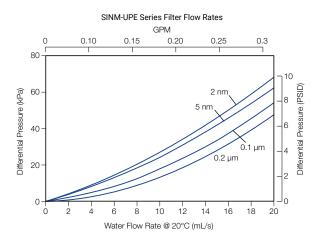


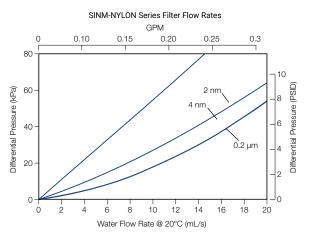


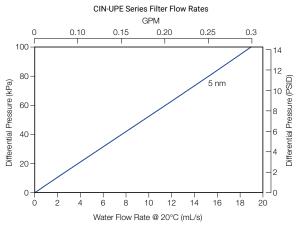




PHOTOGILE POU FLOW CURVES

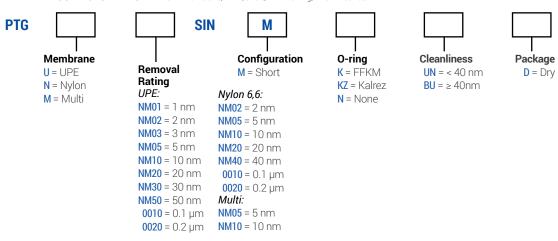






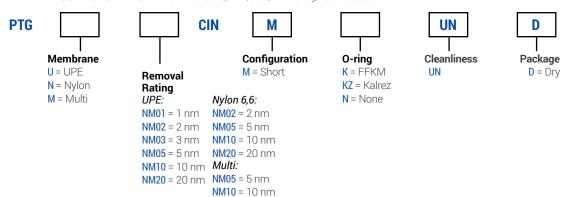
PHOTOGILE PTG SIN ORDERING INFORMATION

EXAMPLE: **PTGUNM02SINMKUNW** = UPE membrane, 2 nm, short, FFKM o-ring, < 40nm device

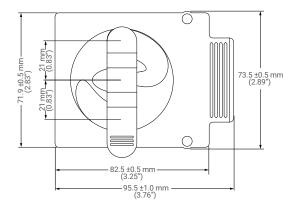


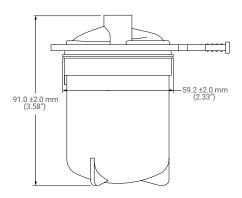
PHOTOGILE PTG CIN ORDERING INFORMATION

EXAMPLE: **PTGUNM02CINMKUNW** = UPE membrane, 2 nm, short, FFKM o-ring, < 50nm device



PHOTOGILE PTG PIN DIMENSIONS





PHOTOGILE PTG PIN ORDERING INFORMATION

EXAMPLE: PTGUNM20PINKUND = UPE membrane, 20 nm, FFKM o-ring, < 40nm device cleanliness





 $0020 = 0.2 \, \mu \text{m}$